

### IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of:

Gregory BREYTA et al.

Confirmation No.: 1035

Serial No.: 10/729,453

Group Art Unit: 1713

Filing Date: December 4, 2003

Examiner: Unassigned

Title: PRECURSORS TO FLUOROALKANOL-CONTAINING OLEFIN MONOMERS,

AND ASSOCIATED METHODS OF SYNTHESIS AND USE

## INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

This is an Information Disclosure Statement submitted for the Examiner's consideration. Applicants respectfully request that the Examiner review and make of record the references identified below.

A PTO-1449 form listing the references accompanies this paper. Applicants would appreciate the Examiner's initialing and returning the form to indicate that the references have been reviewed and made of record. The references are as follows:

U.S. PATENT DOCUMENT				
Document No.	Issue Date or Publication Date	Name of Patentee or Applicant		
3,444,148	5/13/69	Adelman		

F	OREIGN PATENT DOCUMENTS	
Document No.	Publication Date	Country
WO 01/86352	11/15/01	PCT
WO 02/079287	10/10/02	PCT
WO 03/040827	5/15/03	PCT

#### NONPATENT DOCUMENTS

BAE et al. (2003), "Rejuvenation of 248 nm Resist Backbones for 157 nm Lithogrpahy," *Journal of Photopolymer Science and Technology* 14(4):613-620.

FEDYNYSHYN et al. (2001), "High Resolution Fluorocarbon Based Resist for 157-nm Lithography," Advances in Resist Technology And Processing XVIII, Proceedings of SPIE 4345:296-307.

ITO et al. (2001), "Polymer Design for 157 nm Chemically Amplified Resists," Advances In Resist Technology And Processing XVIII, Proceedings Of SPIE 4345:273-284.

KUNZ et al. (2001), "Experimental VUV Absorbance Study of Fluorine-Functionalized Polystyrenes," *Advances in Resist Technology and Processing XVIII, Proceedings of SPIE* 4345:285-295.

URRY et al. (1968), "Multiple Multicenter Reactions of Perfluoro Ketones with Olefins," *The Journal of Organic Chemistry* 33(6):2302-2310.

As the subject application was filed after June 30, 2003, copies of the U.S. patents disclosed in this Information Disclosure Statement are not required and, therefore, are not included.

This Information Disclosure Statement is not intended as a representation that a search has been made, that additional information material to the examination of this application does not exist, or that any of the above references constitutes prior art to the present application within the meaning of 35 USC § 102.

As applicants have not yet received a first Action on the merits, no fee is required for filing this Information Disclosure Statement. If, however, the PTO finds that for some reason a fee is found to be necessary, our Deposit Account No. 18-0580 may be charged therefor.

Respectfully submitted,

By:

Dianne E. Reed

Registration No. 31,292

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10/729,453

December 4, 2003

PTO/SB/21 (08-03)
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Approved for use through 08/30/2003. OMB 0651-0031
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r the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it displays a valid OMB control number.

**Application Number** 

Filing Date

## **TRANSMITTAL FORM**

FORM		First Named Inventor	<b>Gregory BREYTA</b>	et al.
(to be used for all correspondence after initi	al filing)	Art Unit	1713	
to be used for an correspondence after man	" """"g)	Examiner Name	Unassigned	
Mail Stop		Attorney Docket Number	ARC920030074US	31
	ENCLOSU	JRES (Check all that apply		
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I hereby certify that this correspondence is being of envelope addressed to: Commissioner for Patent	leposited with t s, P.O. Box 145	he United States Postal Service wi 50, Alexandria, VA 22313-1450 on	th sufficient postage as fi the date shown below.	rst class mail in an
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# INFORMATION DISCLOSURE STATEMENT BY APPLICANTES

(use as many sheets as necessary)

Sheet	1	of	1

Complete if Known		
Application Number	10/729,453	
Filing Date	December 4, 2003	
First Named Inventor	Gregory BREYTA et al.	
Art Unit	1713	
Examiner Name	Unassigned	
Attorney Docket Number	ARC920030074US1	

	U.S. PATENT DOCUMENTS						
Examiner Initials*	Cite No.	Document No.	Issue Date or Publication Date	Name of Patentee or Applicant of Cited Document	Class	Subclass	Filing Date if Appropriate
	AA	3,444,148	5/13/69	Adelman			

	FOREIGN PATENT DOCUMENTS						
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	AB	WO 01/86352	11/15/01	PCT			
	AC	WO 02/079287	10/10/02	PCT			
	AD	WO 03/040827	5/15/03	PCT			

		OTHER DOCUMENTS — NONPATENT LITERATURE DOCUMENTS			
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	AG	ITO et al. (2001), "Polymer Design for 157 nm Chemically Amplified Resists," Advances In Resist Technology And Processing XVIII, Proceedings Of SPIE 4345:273-284.			
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	AI	URRY et al. (1968), "Multiple Multicenter Reactions of Perfluoro Ketones with Olefins," <i>The Journal of Organic Chemistry</i> 33(6):2302-2310.			

Examiner	Date	
Signature	Considered	

<sup>\*</sup>EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.